

CLAIMS

1. A method of producing a silver nano-structure by means of a scanning tunneling microscope, which comprises using a probe made of silver or a probe having a surface coated with a silver thin film in the scanning tunneling microscope and applying a voltage pulse to the probe so that silver is transferred on a nano-meter scale from the probe onto a surface of a semiconductor substrate.
2. The method of claim 1, wherein the voltage pulse is applied to the probe under conditions of a voltage of ± 3 V to ± 10 V and a pulse width of 10 μ s to 1 s.